

# US Patent & Trademark Office

## Patent Public Search | Text View

United States Patent Application Publication

20250268023

Kind Code

A1

Publication Date

August 21, 2025

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### THIN-FILM TRANSISTOR, DISPLAY APPARATUS INCLUDING THE SAME, AND METHOD OF MANUFACTURING DISPLAY APPARATUS

#### Abstract

Provided are a thin film transistor substrate which include a substrate, a buffer layer and a thin film transistor, a display apparatus including the thin film transistor substrate, and a method of manufacturing the display apparatus including the thin film transistor substrate. The buffer layer includes an inorganic insulating layer. An area ratio of a peak corresponding to an N—H bond in the buffer layer is 0.5% or less based on a total peak area in a Fourier transform infrared spectroscopy (FTIR).

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**Family ID:** 1000008576597

**Appl. No.:** 19/198533

**Filed:** May 05, 2025

#### Foreign Application Priority Data

KR

10-2020-0022370

Feb. 24, 2020

#### Related U.S. Application Data

## Publication Classification

**Int. Cl.:** **H10K59/121** (20230101); **H10D30/67** (20250101); **H10D86/01** (20250101); **H10D86/40** (20250101); **H10D86/60** (20250101); **H10K59/12** (20230101); **H10K77/10** (20230101); **H10K102/00** (20230101)

## U.S. Cl.:

**CPC** **H10K59/1213** (20230201); **H10K77/111** (20230201); H10D30/6758 (20250101); H10D86/0212 (20250101); H10D86/411 (20250101); H10D86/60 (20250101); H10K59/1201 (20230201); H10K2102/311 (20230201)

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## Background/Summary

CROSS-REFERENCE TO RELATED APPLICATION [0001] This application is a divisional application of U.S. patent application Ser. No. 18/508,151 filed on Nov. 13, 2023, which is a divisional application of U.S. patent application Ser. No. 17/034,252 filed on Sep. 28, 2020, now U.S. Pat. No. 11,864,421, which claims the benefit of Korean Patent Application No. 10-2020-0022370, filed on Feb. 24, 2020, in the Korean Intellectual Property Office, the disclosure of which is incorporated herein in its entirety by reference.

### BACKGROUND

#### 1. Field

[0002] One or more embodiments relate to a thin-film transistor, and more particularly, to a thin-film transistor having improved quality of a buffer layer, a display apparatus employing the thin-film transistor and having improved image display quality, and a method of manufacturing the display apparatus.

#### 2. Description of Related Art

[0003] Recently, display apparatuses have been used for various purposes. Further, the display apparatuses have been made thinner and lighter, and thus the display apparatuses have been used in many ways.

[0004] In order to improve the image quality of a display apparatus, improvement in performance of a thin-film transistor inside the display apparatus is also an important factor.

[0005] Therefore, research on improving film quality has been continuously conducted to improve the performance of thin-film transistors.

### SUMMARY

[0006] One or more embodiments provide a display apparatus in which the content of N—H in a buffer layer of a thin film transistor is controlled to improve image display quality, and a method of manufacturing the display apparatus.

[0007] Technical problems to be solved by the present disclosure are not limited to the technical problems mentioned above, and other technical problems not mentioned will be clearly understood by those skilled in the art from the description of the present disclosure.

[0008] Additional aspects will be set forth in part in the description which follows and, in part, will be apparent from the description, or may be learned by practice of the presented embodiments of the disclosure.

[0009] According to one or more embodiments, a thin film transistor substrate may include a

substrate, an active layer disposed on the substrate, a buffer layer disposed between the substrate and the active layer, a source electrode, and a drain electrode, wherein the buffer layer may include an inorganic insulating layer and an area ratio of a peak corresponding to an N—H bond in the material constituting the buffer layer is 0.5% or less based on a total peak area in a Fourier transform infrared spectroscopy (FTIR).

[0010] In an embodiment, the inorganic insulating layer may be one of silicon oxide, silicon nitride and silicon oxynitride.

[0011] In an embodiment, a content of a compound having an N—H bond in the buffer layer may be 0.5 wt % or less based on a total weight of the buffer layer.

[0012] In an embodiment, the buffer layer may be in contact with the active layer, and a content of a compound having an N—H bond in the buffer layer may decrease when a distance from an interface between the buffer layer and the active layer increases.

[0013] In an embodiment, an amount of outgassing hydrogen, measured by thermal desorption spectroscopy (TDS) at a temperature of about 500° C. or higher, may be about  $9 \times 10^{15}$  ea/cm<sup>2</sup> or less.

[0014] In an embodiment, a content of defects including Si—N—Si clusters in the buffer layer may be about  $7.0 \times 10^{17}$  spins/cm<sup>3</sup> or less.

[0015] In an embodiment, the buffer layer may have a single-layer structure or a multi-layer structure.

[0016] In an embodiment, the thin film transistor substrate may further include a second barrier layer disposed between the substrate and the buffer layer.

[0017] In an embodiment, the second buffer layer may include a material different from the buffer layer and includes at least one of silicon oxide and silicon nitride.

[0018] In an embodiment, the active layer may include at least one of an organic semiconductor, an inorganic semiconductor, and a silicon semiconductor.

[0019] In an embodiment, the thin film transistor substrate may further include a first insulating layer on the active layer, and a gate electrode on the first insulating layer.

[0020] In an embodiment, the first insulating layer may be different from the active layer, and may include at least one of SiO<sub>2</sub>, SiN<sub>x</sub>' ( $0 < x' < 2$ ), SiON, Al<sub>2</sub>O<sub>3</sub>, TiO<sub>2</sub>, Ta<sub>2</sub>O<sub>5</sub>, HfO<sub>2</sub>, ZrO<sub>2</sub>, Ba<sub>1-y'-z'</sub>Sr<sub>y'</sub>Ti<sub>z'</sub>O<sub>3</sub>(BST) ( $0 < y' < 1$ ,  $0 < z' < 1$ ,  $0 < y' + z' < 1$ ), and PbZr<sub>w'</sub>Ti<sub>1-w'</sub>O<sub>3</sub>(PZT) ( $0 < w' < 1$ ).

[0021] According to one or more embodiments, a display apparatus may include a thin film transistor including a substrate, an active layer disposed on the substrate, a buffer layer disposed between the substrate and the active layer, a source electrode, and a drain electrode, wherein the buffer layer includes an inorganic insulating layer and an area ratio of a peak corresponding to an N—H bond in the buffer layer is 0.5% or less based on a total peak area in a Fourier transform infrared spectroscopy (FTIR) and a light-emitting device including a first electrode, a second electrode facing the first electrode, and an interlayer between the first electrode and the second electrode.

[0022] One of the source electrode and drain electrode of the thin film transistor may be electrically connected to the first electrode of the light-emitting device.

[0023] In an embodiment, the interlayer may include a light-emitting layer, and may optionally include at least one of a hole transport layer disposed between the first electrode and the light-emitting layer and an electron transport layer disposed between the light-emitting layer and the second electrode.

[0024] According to one or more embodiments, a method of manufacturing a display apparatus includes providing a substrate, forming a buffer layer on the substrate, and forming an active layer on the buffer layer, wherein the buffer layer includes an inorganic insulating layer, and an area ratio of a peak corresponding to a N—H bond in the buffer layer is 0.5% or less based on a total peak area in a Fourier transform infrared spectroscopy (FTIR).

[0025] In an embodiment, the forming the buffer layer may be performed by a deposition process, and a power applied for the deposition of the buffer layer may be about 6 KW to about 10 KW.

[0026] In an embodiment, the forming the buffer layer may be performed by a deposition process, and process pressure in the deposition process may be about 700 Torr to about 900 Torr.

[0027] In an embodiment, the forming the buffer layer may be performed by a deposition process, and a reaction gas in the deposition process may include nitrous oxide (N.sub.2O) gas and silane (SiH.sub.4) gas.

[0028] In an embodiment, a flow ratio of the nitrous oxide (N.sub.2O) gas and the silane (SiH.sub.4) gas may be about 20:1 to about 35:1.

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## Description

### BRIEF DESCRIPTION OF THE DRAWINGS

[0029] The above and other aspects, features, and advantages of certain embodiments of the disclosure will be more apparent from the following description taken in conjunction with the accompanying drawings, in which:

[0030] FIG. 1 is a schematic view illustrating a thin-film transistor according to an embodiment of the present disclosure;

[0031] FIG. 2 is a schematic perspective view illustrating a display apparatus according to an embodiment of the present disclosure;

[0032] FIG. 3 is a schematic cross-sectional view illustrating a display apparatus according to an embodiment of the present disclosure;

[0033] FIG. 4 is a schematic block diagram illustrating the configuration of an electronic appliance according to an embodiment of the present disclosure;

[0034] FIGS. 5A and 5B are schematic perspective views illustrating electronic appliances according to an embodiment of the present invention.

[0035] FIG. 6A is a graph analyzing FTIR of Examples 1 to 2 and Comparative Examples 1 to 3, FIG. 6B is an enlarged graph of the N—H peak portion of an area A in the graph of FIG. 6A, and FIG. 6C is a graph for measuring a change in threshold voltage (V<sub>th</sub>) according to ratio of an N—H area to a FTIR peak area;

[0036] FIG. 7 is a graph illustrating a change in the number of defects in a buffer layer when the area ratios of peaks to NH bonds are 0.3%, 0.54%, 0.73%, 0.99%, and 1.01%, respectively, based on the total peak area in the FTIR analysis spectrum; and

[0037] FIG. 8 is a graph illustrating a change in the amount of outgassing hydrogen according to a change in the area ratios (hereinafter, N—H component ratios) of the peaks for the N—H bond in the FTIR analysis spectrum by TDS analysis.

### DETAILED DESCRIPTION

[0038] Reference will now be made in detail to embodiments, examples of which are illustrated in the accompanying drawings, wherein like reference numerals refer to like elements throughout. In this regard, the present embodiments may have different forms and should not be construed as being limited to the descriptions set forth herein. Accordingly, the embodiments are merely described below, by referring to the figures, to explain aspects of the present description. As used herein, the term “and/or” includes any and all combinations of one or more of the associated listed items. Throughout the disclosure, the expression “at least one of a, b or c” indicates only a, only b, only c, both a and b, both a and c, both b and c, all of a, b, and c, or variations thereof.

[0039] Hereinafter, embodiments of the present disclosure will be described in detail with reference to the accompanying drawings. When a description is made with reference to the drawings, the same or corresponding components will be given the same reference numerals, and redundant description thereof will be omitted.

[0040] In the following embodiments, such terms as “first,” “second,” etc., are not be limited, and terms are used only to distinguish one component from another, not for purposes of limitation.

[0041] In the following embodiments, an expression used in the singular encompasses the expression of the plural, unless it has a clearly different meaning in the context.

[0042] In the following embodiments, the terms “comprises” and/or “has,” when used in this specification, specify the presence of stated features, integers, steps, operations, elements, and/or components, but do not preclude the presence or addition of one or more other features, integers, steps, operations, elements, components, and/or groups thereof.

[0043] In the following embodiments, when a component, such as a layer, a film, a region, or a plate, is referred to as being “on” another component, the component may be directly on the other component or intervening components may be present thereon.

[0044] In the drawings, the size of components may be exaggerated or reduced for convenience of description. For example, since the size and thickness of each component illustrated in the drawings are arbitrarily illustrated for convenience of description, the present invention is not necessarily limited to those illustrated.

[0045] When any embodiment may be implemented differently, a specific process order may be performed differently from the described order. For example, two subsequent processes may be performed substantially simultaneously, or may be performed in an order opposite to that described.

[0046] In the following embodiments, assuming that films, regions, components, etc. are connected, this includes not only a case where films, regions, and components are directly connected, but also a case where films, regions, and components are indirectly connected by interposing other films, regions, and components therebetween. For example, in this specification, assuming that films, regions, components, etc. are electrically connected, this includes not only a case where films, regions, and components are electrically connected directly, but also a case where films, regions, and components are electrically connected indirectly by interposing other films, regions, and components therebetween.

[0047] FIG. 1 is a schematic view illustrating a thin film transistor according to an embodiment of the present disclosure.

[0048] Referring to FIG. 1, a thin film transistor TR includes: a substrate **100**; an active layer **120** disposed on the substrate **100**; a buffer layer **110** disposed between the substrate **100** and the active layer **120**; a source electrode (not shown, refer to FIG. 2); and a drain electrode (not shown, refer to FIG. 2), wherein the buffer layer **110** includes an inorganic insulating layer, for example, silicon oxide, silicon nitride and silicon oxynitride; and the area ratio of a peak corresponding to a N—H bond in the buffer layer is 0.5% or less based on the total peak area in a Fourier transform infrared spectroscopy (FTIR).

[0049] The substrate **100** may include various materials such as glass, metal, metal oxide, metal nitride, or plastic. For example, the substrate **100** may include polyethersulfone, polyacrylate, polyetherimide, polyethylenenaphthalate, polyethyleneterephthalate, polyphenylene sulfide, polyarylate, polyimide, polycarbonate, or cellulose acetate propionate.

[0050] The substrate **100** may have flexible, rollable, or bendable characteristics. The substrate **100** may have a multi-layer structure including a plurality of layers, and the layers may include different materials from each other.

[0051] The buffer layer **110** may be disposed on the substrate **100** to provide a flat upper surface and function to block impurities from entering into the active layer **120**. The buffer layer **110** may be formed as a single layer or multiple layers including an inorganic material such as silicon nitride (SiN.sub.x) (0<x<2), and/or silicon oxide (SiO.sub.y) (0<y<3).

[0052] The buffer layer **110** is disposed adjacent to the active layer **120** while performing the above-described functions, and thus may greatly affect the characteristics of the thin film transistor which is formed using the active layer **120**. Therefore, improvement in film quality (roughness) of

the buffer layer **110** is important.

[0053] However, conventionally, pin holes in the buffer layer **110** having improved film quality are less than that in the buffer layer having ordinary film quality, and thus a large amount of hydrogen is piled up under the active layer **120** during a dehydrogenation process of the active layer **120** because the hydrogen in the active layer **120** cannot out-diffuse through the buffer layer **110** having improved film quality. Accordingly, in an excimer laser annealing (ELA) process of applying an excimer laser when forming the active layer **120**, the active layer is damaged due to rapid outgassing of hydrogen through the active layer **120**. Such a problem causes pixel defects.

[0054] Further, a leakage current in the off current ( $I_{\text{sub.off}}$ ) area increases, a gate bias increases due to an increase in electron traps in the buffer layer, and a hot carrier phenomenon occurs, thereby causing a problem of increasing leakage at a drain junction.

[0055] In the thin film transistor TR according to an embodiment of the present disclosure, the area ratio of the FTIR peak corresponding to the N—H bond in the entire material constituting the buffer layer **110** is limited to 0.5% or less, thereby solving the aforementioned problem.

[0056] That is, when the N—H bond in the above range is maintained in the buffer layer **110**, a hydrogen pile up phenomenon under the active layer **120** is suppressed during a dehydrogenation process of the active layer **120**, thereby minimizing hydrogen outgassing.

[0057] In an embodiment, the content of a compound having a N—H bond in the buffer layer **110** may be 0.5 wt % or less based on the total weight of the buffer layer.

[0058] In an embodiment, the buffer layer **110** is in direct contact with the active layer **120**, and the content of the compound having a N—H bond in the buffer layer **110** decreases when a distance from an interface between the buffer layer **110** and the active layer **120** increases (in a dotted arrow direction).

[0059] Thus, defects of the buffer layer influencing the active layer may be reduced.

[0060] In an embodiment, the amount of outgassing hydrogen, measured by thermal desorption spectroscopy (TDS) at a temperature of about 500° C. or higher, may be about  $9 \times 10^{15}$  ea/cm<sup>2</sup> or less.

[0061] In an embodiment, the content of defects including Si—N—Si clusters in the buffer layer **110** may be about  $7.0 \times 10^{17}$  spins/cm<sup>3</sup> or less.

[0062] The Si—N—Si cluster may act as a defect in the buffer layer **110** to cause problems such as leakage and increase in gate bias at the above-described drain junction. The thin film transistor TR according to an embodiment of the present disclosure may employ the aforementioned configuration, thereby minimize defects.

[0063] A threshold voltage  $V_{\text{sub.th}}$  may be reduced due to the reduction of defects, thus a momentary afterimage of the display apparatus may also be reduced, and a gate bias may be reduced to reduce the defective rate of the display apparatus.

[0064] In an embodiment, the buffer layer **110** may have a single-layer structure or a multi-layer structure.

[0065] That is, the thin film transistor TR may further include a second buffer layer **102** disposed between the buffer layer **110** and the substrate **100**. For example, the second buffer layer may include a material different from the buffer layer, and may include at least one of silicon oxide and silicon nitride.

[0066] For example, the buffer layer **110** may include silicon oxide, and the second buffer layer **102** may include silicon nitride.

[0067] The active layer **120** may be disposed on the buffer layer **110**. The active layer **120** may include at least one of an organic semiconductor, an inorganic semiconductor, and a silicon semiconductor.

[0068] In an embodiment, the thin film transistor TR may further include a barrier layer **101** disposed between the substrate **100** and the buffer layer **110**.

[0069] For example, the barrier layer **101** may be disposed between the second buffer layer **102**

and the substrate **100**. In this case, the barrier layer **101** may include a material different from the second buffer layer **110**.

[0070] In an embodiment, the barrier layer **101** may include silicon oxide.

[0071] FIG. **2** is a schematic perspective view illustrating a display apparatus according to an embodiment of the present disclosure.

[0072] Referring to FIG. **2**, a display apparatus **1** includes a display area DA and a non-display area NDA surrounding the display area DA. Various display elements such as an organic light-emitting diode (OLED) may be disposed in the display area DA. Various conductive lines for transmitting electrical signals to be applied to the display area DA including the thin film transistor may be disposed in the non-display area NDA. Although one thin film transistor may be disposed in the non-display area NDA, a plurality of thin film transistors and a plurality of capacitors may be further provided in the non-display area NDA, and scan lines, data lines, and power supply lines which are connected to the thin film transistors may be further provided in the non-display area NDA.

[0073] Although FIG. **2** shows the display apparatus **1** having a rectangular display area DA, but the present invention is not limited thereto. The display area DA may have a circular shape, an elliptical shape, or a polygonal shape such as a triangle or a pentagon.

[0074] Although it is shown in FIG. **2** that the display apparatus **1** is a flat display apparatus, the display apparatus **1** may be implemented in various forms, such as a flexible, foldable, and rollable forms.

[0075] Hereinafter, for convenience of description, as the display apparatus **1** according to an embodiment of the present disclosure, an organic light-emitting display apparatus will be described as an example, but the display apparatus of the present disclosure is not limited thereto. As another embodiment, various types of display apparatus, such as an Inorganic light-emitting display and a quantum dot light-emitting display, may be used.

[0076] FIG. **3** is a schematic cross-sectional view illustrating a display apparatus according to an embodiment of the present disclosure.

[0077] Referring to FIG. **3**, the display apparatus **1** according to an embodiment of the present disclosure includes: a light-emitting device OLED including a first electrode **180**, a second electrode **210** facing the first electrode **180**, and an interlayer **200** between the first electrode **180** and the second electrode **210**; and the aforementioned thin film transistor TR. One of the source electrode **160** and drain electrode **161** of the thin film transistor TR is electrically connected to the first electrode **180** of the light-emitting device OLED.

[0078] Descriptions of the substrate **100**, the buffer layer **110**, and the active layer **120** refer to the above descriptions.

[0079] In an embodiment, a first insulating layer **130** may be disposed on the active layer **120** to cover the active layer **120**, and a gate electrode **140** may be disposed on the first insulating layer **130**.

[0080] The first insulating layer **130** may be different from the active layer **120**, and may include at least one of  $\text{SiO}_2$ ,  $\text{SiN}_x$  ( $0 < x < 2$ ),  $\text{SiON}$ ,  $\text{Al}_2\text{O}_3$ ,  $\text{TiO}_2$ ,  $\text{Ta}_2\text{O}_5$ ,  $\text{HfO}_2$ ,  $\text{ZrO}_2$ ,  $\text{Ba}_{1-y-z}\text{Sr}_y\text{Ti}_z\text{O}_3$  (BST) ( $0 < y < 1$ ,  $0 < z < 1$ ,  $0 < y + z < 1$ ), and  $\text{PbZr}_w\text{Ti}_{1-w}\text{O}_3$  (PZT) ( $0 < w < 1$ ). The first insulating layer **130** may be formed as a single layer or multiple layers. The first insulating layer **130** may be an inorganic insulating layer. The first insulating layer **130** may function as a gate insulator (GI).

[0081] The gate electrode **140** may be formed as a single layer or multiple layers including aluminum (Al), platinum (Pt), palladium (Pd), silver (Ag), magnesium (Mg), gold (Au), nickel (Ni), neodymium (Nd), iridium (Ir), chromium (Cr), lithium (Li), calcium (Ca), molybdenum (Mo), titanium (Ti), tungsten (W), copper (Cu), or any combination thereof. The gate electrode **140** may be connected to a gate line that applies an electrical signal to the gate electrode **140**.

[0082] A source electrode **160** and/or a drain electrode **161** may be disposed on the gate electrode

**140** with the second insulating layer **150** disposed therebetween. The source electrode **160** and/or the drain electrode **161** may be electrically connected to the active layer **120** through a contact hole formed in the second insulating layer **150** and the first insulating layer **130**. The second insulating layer **150** may function as an interlayer insulating layer.

[0083] The second insulating layer **150** may be an inorganic insulating layer. The second insulating layer **150** may be formed as a single layer or multiple layers including at least one selected from SiO.sub.2, SiN.sub.x, SiON, Al.sub.2O.sub.3, TiO.sub.2, Ta.sub.2O.sub.5, HfO.sub.2, ZrO.sub.2, BST, and PZT. In another embodiment, the second insulating layer **150** may be an organic insulating layer.

[0084] The source electrode **160** may be formed as a single layer or multiple layers including aluminum (Al), platinum (Pt), palladium (Pd), silver (Ag), magnesium (Mg), gold (Au), nickel (Ni), neodymium (Nd), iridium (Ir), chromium (Cr), lithium (Li), calcium (Ca), molybdenum (Mo), titanium (Ti), tungsten (W), copper (Cu), or any combination thereof. For example, the source electrode **160** may be formed as three layers of Mo/Al/Mo, Mo/Al/Ti, and Ti/Al/Ti. In an alternative embodiment, the source electrode **160** may be formed of Mo/Al/Ti. For a description of the drain electrode **161**, refer to the description of the source electrode **160**. For example, the source electrode **160** and the drain electrode **161** may be formed of two or more layers.

[0085] A third insulating layer **170** may be disposed on the second insulating layer **150**. In an embodiment, the third insulating layer **170** may also be disposed on the source electrode **160** and the drain electrode **161**. The third insulating layer **170** may have a structure that covers the thin film transistor TR1.

[0086] The third insulating layer **170** may be formed as a single organic insulating layer or a plurality of organic insulating layers, each having a flat upper surface. The third insulating layer **170** may include a general-purpose polymer (PMMA or PS), a polymer derivative having a phenol group, an acrylic polymer, an imide polymer, an aryl ether polymer, an amide polymer, a fluorine polymer, a p-xylene polymer, a vinyl alcohol-based polymer, or a blend thereof. For example, the third insulating layer **170** may include polyimide, polyamide, or acrylic resin.

[0087] The first electrode **180** of the light-emitting device OLED electrically connected to the thin film transistor TR is provided on the third insulating layer **170**. The first electrode **180** may be provided corresponding to the display area DA.

[0088] When the light-emitting device OLED is a front light-emitting device, the first electrode **180** may be formed as a reflective electrode. The reflective electrode may include a reflective layer including Ag, Mg, Al, Pt, Pd, Au, Ni, Nd, Ir, Cr, or a compound thereof, and a transparent or translucent electrode layer formed on the reflective layer. When the light-emitting device OLED is a back light-emitting device, the first electrode **180** includes a transparent material such as ITO, IZO, ZnO, or In.sub.2O.sub.3, and may be formed as a transparent or translucent electrode.

[0089] A fourth insulating layer **191** located on the first electrode **180** and located to contact the third insulating layer **170** from the outside of the first electrode **180** may be provided. The fourth insulating layer **191** may include a second opening exposing at least a portion of the first electrode **180**, for example, a central portion thereof. Thus, the fourth insulating layer **191** may serve to define a light-emitting area of a pixel.

[0090] The fourth insulating layer **191** may include a siloxane-based polymer, an imide-based polymer, an amide-based polymer, an olefin-based polymer, an acrylic-based polymer, a phenol-based polymer, or any combination thereof.

[0091] The light-emitting device OLED may include a first electrode **180** disposed on the third insulating layer **170**, a second electrode **210** facing the first electrode **180**, and an interlayer **210** disposed between the first electrode **180** and the second electrode **210**.

[0092] The interlayer **200** may include a light-emitting layer that emits light, and may further include at least one functional layer of a hole injection layer (HIL), a hole transport layer (HTL), an electron transport layer (ETL), and an electron injection layer (EIL). However, the present



embodiment is not limited thereto, and various functional layers may be further disposed on the first electrode **180**.

[0093] The light-emitting layer may be a red light-emitting layer, a green light-emitting layer, or a blue light-emitting layer. Alternatively, the light-emitting layer may have a multilayer structure in which a red light-emitting layer, a green light-emitting layer, and a blue light-emitting layer are stacked to emit white light, or may have a single layer structure including a red light-emitting material, a green light-emitting material, and a blue light-emitting material.

[0094] In an embodiment, the interlayer **200** may be provided only in the light-emitting area AA by using a mask having an opening corresponding to the light-emitting area AA of the display apparatus **1**, for example, a fine metal mask (FMM).

[0095] In another embodiment, the light-emitting layer of the interlayer **200** is provided only in the light-emitting area AA by using a fine metal mask (FMM) having an opening corresponding to the light-emitting area AA of the display apparatus **1**, and other functional layers of the interlayer **200** may be provided on the front surfaces of the light-emitting area AA and the non-light-emitting area NAA by using an open mask.

[0096] The second electrode **210** may be provided on the interlayer **200**. The second electrode **210** may be a reflective electrode, a transparent electrode, or a translucent electrode. For example, the second electrode **210** may include a metal having a small work function, and may include Li, Ca, LiF/Ca, LiF/Al, Al, Ag, Mg, or any combination thereof.

[0097] Although not shown in FIG. **3**, a counter substrate may be further provided on the second electrode **210**. For a description of the counter substrate, refer to the description of the substrate **100**.

[0098] Although not shown in FIG. **3**, a black matrix BM and a color filter CF may be disposed on the surface of the counter substrate facing the substrate **100**. The color filter CF may be disposed to correspond to the light-emitting area AA of the display apparatus **1**. The black matrix BM may be disposed to correspond to an area except for the light-emitting area AA of the display apparatus **1**.

[0099] Although not shown in FIG. **3**, a protective layer may be further provided between the counter substrate and the second electrode **210**. The protective layer may be a single layer or multiple layers of an inorganic layer and/or an organic layer.

[0100] Although not shown in FIG. **3**, various functional layers may be further provided on the counter substrate. For example, the functional layer may be an anti-reflection layer that minimizes reflection on the upper surface of the counter substrate, or an anti-fouling layer that prevents contamination such as a user's handprint (for example, a fingerprint mark).

[0101] In another embodiment, a thin film encapsulation layer, instead of the counter substrate, may be disposed on the substrate **100**. The thin film encapsulation layer may include an inorganic encapsulation layer including at least one inorganic material and an organic encapsulation layer including at least one organic material. In some embodiment, the thin film encapsulation layer may be provided as a structure in which a first inorganic encapsulation layer/an organic encapsulation layer/a second inorganic encapsulation layer are stacked.

[0102] Hereinafter, a method of manufacturing a display apparatus will be described with reference to FIG. **1**.

[0103] A method of manufacturing a display apparatus according to an embodiment of the present disclosure includes the steps of: providing a substrate **100**; forming a buffer layer **110** on the substrate **100**; and forming an active layer **120** on the buffer layer **110**, wherein the buffer layer **110** includes at least one of silicon oxide and silicon nitride, and an area ratio of a peak corresponding to a N—H bond in the material constituting the buffer layer is 0.5% or less based on a total peak area in a Fourier transform infrared spectroscopy (FTIR).

[0104] Descriptions of the substrate **100**, the buffer layer **110**, the active layer **120**, and the like, refer to the above descriptions.

[0105] The step of forming the buffer layer **110** may be performed by a deposition process, and the

power applied for the deposition of the buffer layer may be about 6 KW to about 10 KW. As the power applied for the deposition decreases, the content of N—H bonds in the buffer layer **110** decreases.

[0106] The step of forming the buffer layer **110** may be performed by a deposition process, and the process pressure in the deposition process may be about 700 Torr to about 900 Torr. As the process pressure decreases, the content of N—H bonds in the buffer layer **110** decreases.

[0107] The step of forming the buffer layer **110** may be performed by a deposition process, and the reaction gas in the deposition process may include nitrous oxide (N.sub.2O) gas and silane (SiH.sub.4) gas.

[0108] For example, the flow rate of nitrous oxide (N.sub.2O) gas may be about 40,000 sccm to about 70,000 sccm (standard cubic centimeter per minute). For example, the flow rate of silane (SiH.sub.4) gas may be about 1500 sccm to about 3000 sccm. As the flow rate of nitrous oxide gas increases or the flow rate of silane gas decreases, the content of N—H bonds in the buffer layer **110** decreases.

[0109] The flow ratio of the nitrous oxide (N.sub.2O) gas and the silane (SiH.sub.4) gas is about 20:1 to about 35:1.

[0110] The display apparatus **1** may be implemented as an electronic appliance **1000** such as a mobile phone, a video phone, a smart phone, a smart pad, a smart watch, a tablet PC, a notebook computer, a computer monitor, a television, a terminal for digital broadcasting, a personal digital assistant (PDA), a portable multimedia player (PMP), a head mounted display (HMD), or car navigator.

[0111] FIG. **4** is a schematic block diagram illustrating the configuration of an electronic appliance according to an embodiment of the present disclosure. FIGS. **5A** and **5B** are schematic perspective views illustrating electronic appliances according to an embodiment of the present invention.

[0112] Referring to FIG. **4**, an electronic appliance **1000** may include a processor **1010**, a memory **1020**, a storage **1030**, an input/output **1040**, a power supply **1050**, and a display apparatus **1060**. In this case, the display apparatus **1060** may correspond to the display apparatus **1** of FIG. **2**. The electronic device **1000** may communicate with a video card, a sound card, a memory card, or an USB device, or may further include several ports capable of communicating with other systems.

[0113] In an embodiment, as shown in FIG. **5A**, the electronic appliance **1000** may be implemented as a television. In another embodiment, as shown in FIG. **5B**, the electronic appliance **1000** may be implemented as a smart phone. However, these are exemplary, and the electronic appliance **1000** is not limited thereto.

[0114] Next, the change in N—H component ratio in a thin film layer according to adjustment of process parameters when manufacturing a thin film transistor will be described with reference to FIGS. **6A** to **6C**.

[0115] The graph represented by Comparative Example 1 is a FTIR graph of Sample 1. In Sample 1, a buffer layer was deposited under the conditions that the power applied for deposition was 5000 W, the process pressure was 900 Torr, the flow rate of N.sub.2O gas was 90000 sccm, and the flow rate of SiH.sub.4 gas was 1500 sccm.

[0116] The graph represented by Comparative Example 2 is a FTIR graph of Sample 2. In Sample 2, a buffer layer was deposited under the conditions that the power applied for deposition was 6000 W, the process pressure was 900 Torr, the flow rate of N.sub.2O gas was 99000 sccm, and the flow rate of SiH.sub.4 gas was 2200 sccm.

[0117] The graph represented by Comparative Example 3 is a FTIR graph of Sample 3. In Sample 3, a buffer layer was deposited under the conditions that the power applied for deposition was 6500 W, the process pressure was 1000 Torr, the flow rate of N.sub.2O gas was 80000 sccm, and the flow rate of SiH.sub.4 gas was 1800 sccm.

[0118] The graph represented by Example 1 is a FTIR graph of Sample 4. In Sample 4, a buffer layer was deposited under the conditions that the power applied for deposition was 8000 W, the

process pressure was 1000 Torr, the flow rate of N.sub.2O gas was 60,000 sccm, and the flow rate of SiH.sub.4 gas was 2000 sccm.

[0119] The graph represented by Example 2 is a FTIR graph of Sample 5. In Sample 5, a buffer layer was deposited under the conditions that the power applied for deposition was 7000 W, the process pressure was 900 Torr, the flow rate of N.sub.2O gas was 70,000 sccm, and the flow rate of SiH.sub.4 gas was 1600 sccm.

[0120] Referring to FIG. 6C, when considering the ratio of an N—H area to a FT-IR peak area, it may be ascertained that the peak value is 0.5 or less only in the graph of Example 1. Referring to FIGS. 6A and 6B, the area of the N—H peak in Example 1 was about 0.18% based on the total peak area, and the area of the N—H peak in Example 2 was about 0.3% based on the total peak area.

[0121] That is, the N—H component ratio may be obtained by Equation 1 below:

[00001]

$$\text{area}[N - H] / (\text{area}[Si - O - Si] + \text{area}[Si - H] + \text{area}[N - H] + \text{area}[SiO - H]) \times 100 \quad < \text{Equation 1} >$$

[0122] Moreover, referring to FIG. 6C, it may be ascertained that the V.sub.th value in Example 1 is remarkably lower than those in Comparative Examples 1 to 3.

[0123] Next, the change in film quality of the buffer layer according to the change in area ratio of the peak corresponding to the N—H bond in the FTIR analysis spectrum will be described with reference to FIG. 7.

[0124] Referring to FIG. 7, it may be ascertained that as the area ratio of the peak corresponding to the N—H bond, that is, the N—H component ratio, decreases, the number of defects per unit area of the buffer layer decreases. In particular, it may be ascertained that when N—H component ratio is 0.5% or less, the number of defects remarkably decreases.

[0125] Next, the change in the amount of outgassing hydrogen according to the change in area ratio (hereinafter, N—H component ratio) of the peak corresponding to the N—H bond in the FTIR analysis spectrum by TDS analysis will be described with reference to FIG. 8.

[0126] Referring to FIG. 8, it may be ascertained that, first, at low temperature, the difference in the amount of outgassing hydrogen due to the difference in the N—H component ratio is not large. However, it may be ascertained that, gradually heating up, the difference in the amount of outgassing hydrogen is remarkably large at a temperature of 500° C. or higher, the amount of outgassing hydrogen gradually decreases as the N—H component ratio decreases, and the amount of outgassing hydrogen remarkably decreases when the N—H component ratio is 0.5% or less.

[0127] According to various embodiments of the present disclosure, the N—H content in the buffer layer of the thin film transistor may be controlled to reduce defects in the buffer layer and reduce the amount of outgassing hydrogen. Further, the present disclosure may provide a display apparatus in which image display quality is improved, and a method of manufacturing the display apparatus.

[0128] However, the above-described effects are exemplary, and effects according to embodiments will be described in detail through the following contents.

[0129] It should be understood that embodiments described herein should be considered in a descriptive sense only and not for purposes of limitation. Descriptions of features or aspects within each embodiment should typically be considered as available for other similar features or aspects in other embodiments. While one or more embodiments have been described with reference to the figures, it will be understood by those of ordinary skill in the art that various changes in form and details may be made therein without departing from the spirit and scope as defined by the following claims.

## Claims

- 1.** A method of manufacturing a display apparatus, the method comprising: providing a substrate; forming a buffer layer on the substrate; and forming an active layer on the buffer layer, wherein the buffer layer includes an inorganic insulating layer and an area ratio of a peak corresponding to an N—H bond in the buffer layer is 0.5% or less based on a total peak area in a Fourier transform infrared spectroscopy (FTIR).
  - 2.** The method of claim 1, wherein the forming of the buffer layer is performed by a deposition process and a power applied for the deposition of the buffer layer is about 6 KW to about 10 KW.
  - 3.** The method of claim 1, wherein the forming of the buffer layer is performed by a deposition process and process pressure in the deposition process is about 700 Torr to about 900 Torr.
  - 4.** The method of claim 1, wherein the forming of the buffer layer is performed by a deposition process and a reaction gas in the deposition process includes nitrous oxide (N<sub>2</sub>O) gas and silane (SiH<sub>4</sub>) gas.
  - 5.** The method of claim 4, wherein a flow ratio of the nitrous oxide (N<sub>2</sub>O) gas and the silane (SiH<sub>4</sub>) gas is about 20:1 to about 35:1.
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